

Sematech Lithography Forum,
Imprint Session,
Introduction,

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'NanoPrinting' comes in many forms

- SFIL
- Soft Lithography
- NIL
- LADI
- Etc.

NanoPrinting has demonstrated an unbelievably attractive combination of minimum feature size, throughput and cost

- 10nm MFS, $>1\text{cm}^2/\text{s}$, \$1.5M

Nanoprinting is a classic Disruptive Technology

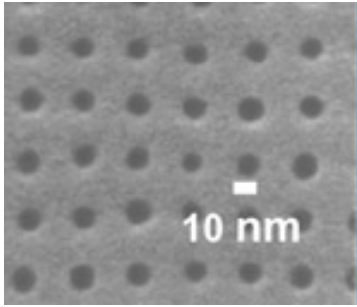
- It may well first find its way into semiconductor manufacturing at non critical levels and then migrate to the critical levels.



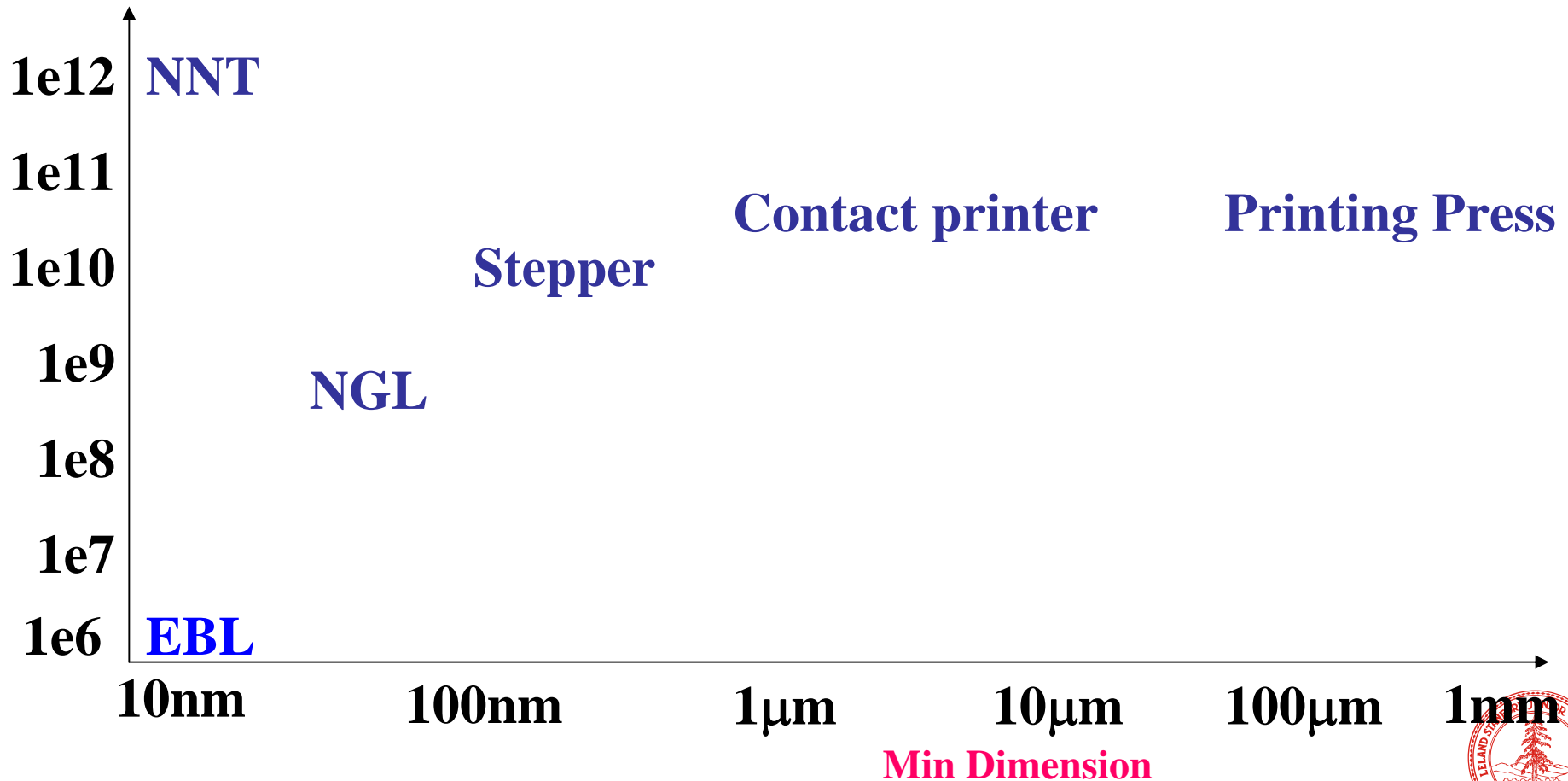
First International Conference on

NNT

Nanoimprint
and Nanoprint
Technology



#MFS/second



Hangups (justifiable?) include:

- Overlay, defects and template making
- We are to discuss these during this session

My Take:

- Overlay should be easier than in a scanner because we can monitor the entire field of view and use local temperature control to correct for distortion,
- Defects have never stopped us,
- Template fabrication is no more difficult than for a current optical reticle with RET features. Inspection may be the most serious challenge.

